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Study of Chloride in the Passive Film on Aluminum Prior to Pitting Corrosion

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Introduction: Aluminum (Al) experiences pitting corrosion at a critical pitting potential in 0.1 M NaCl ($E_{pit} \sim -0.68 \pm 0.02 \text{ V}_{sce}$). However, interactions between aggressive anions, such as chlorides (Cl), with the passivating Al oxide may occur at potentials (E) < E_{pit} .(1) This research examines the interactions between Cl and the passive film on Al at E < E_{pit} in order to determine the role of Cl in the breakdown of passivity.

Methods and Materials: High purity polycrystalline Al (99.997% Al) was used for testing. Al samples were tested in deaerated 0.1 M NaCl solution at room temperature. A three-electrode electrochemical cell, with a saturated calomel reference electrode, was used. The samples were potentiostatically polarized at potentials below E_{pit} of Al, and were held at each potential for 3 hours. Surface analysis of the anodically polarized samples were conducted using X-ray photoelectron spectroscopy (XPS) with Mg K_{α} X-rays, and X-ray absorption near edge spectra (XANES) to record changes and shifts in the K-edge structure of Cl (2833 eV). Both electron yield and X-ray fluorescence XANES were recorded.

Results and Conclusions: Two distinct peaks were observed in the electron yield spectra of Cl. The Cl XANES peak measured by electron yield at 2833 eV, I_e(surface), was attributed to Cl⁻ on the surface of the Al oxide, while the peak at 2836 eV, I_e(oxide), is associated with CI within the Al oxide, or at the oxide/metal interface. An increase and then a decrease in I_e(surface) during polarization from -0.950 to -0.800 V suggests an increasing and a diminishing surface coverage by Cl, as shown in Figure 1. Further polarization from -0.800 to -0.750 V produced increases in I_e(surface), which reflects a renewed surface coverage by Cl⁻. Moreover, I_e(oxide) also increased during anodic polarization from -0.850 to -0.750 V (Figure 2). The increase in I_e(oxide) can be attributed to Cl incorporation into the oxide. However, anodic polarization from -0.750 to -0.700 V resulted in a decrease in I_e(oxide). Similar measurements of surface and bulk Cl were recorded by XPS (Figures 1 and 2). Such a decrease in measured I_c(oxide) can be explained by, albeit not limited to: i) oxide thinning during polarization, where the oxide dissolution rate is greater than the rate of Cl uptake into the oxide, ii) oxide thickening that leads to increased attenuation of the secondary electron signal from Cl anions, which migrated from the solution/oxide interface to the oxide/metal interface, or iii) migration of Cl from the surface toward the oxide/metal interface resulting in a loss of signal due to attenuation. All oxide thickness, as measured by XPS, remained relatively constant during anodic polarization from -0.950 to -0.800 V. However, the oxide thickness decreased from approximately 5 nm to 3.8 nm during polarization from -0.800 to -0.750 V.

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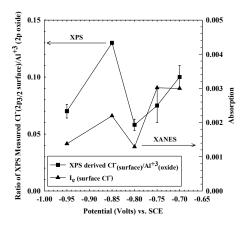


Figure 1: I_e (surface) and XPS for Al measured in Figure 1: I_e (surface) and XPS for Al measured in 0.1 M NaCl.

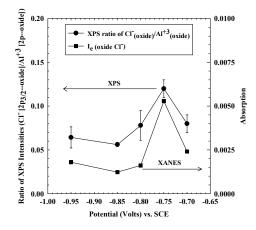


Figure 2: I_e(oxide) and XPS for Al measured in 0.1 M NaCl.